

Niobium-Doped Titania Photocatalyst Film Prepared via a Nonaqueous Sol-Gel Method

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Niobium-doped Titanium dioxide (Nb:TiO₂) transparent films were successfully deposited on glass substrates using a non-aqueous sol-gel spin coating technique. The effect of Nb concentration on the structural and photocatalytic properties of Nb:TiO₂ films was studied using X-ray diffraction (XRD), scanning electron microscopy (SEM), atomic force microscopy (AFM), and UV visible spectroscopy. The films with 12 at.% (atomic percent) Nb doped TiO₂ showed excellent photocatalytic activity through 97.3% degradation of methylene blue (MB) after 2 h of UV irradiation.

I. Introduction

THE anatase polymorph of TiO₂ with band gap ~3.2 eV has been extensively investigated as a semiconductor material for photocatalysis applications due to its chemical inertness, abundance in nature, nontoxicity, biocompatibility, low cost, strongly oxidative nature, and manufacturability at atmospheric conditions. TiO₂ has also been used in sensor devices, self-cleaning applications, bactericidal treatment, dye-sensitized solar cells, drug delivery, and in other bio applications.¹

Over the past few years, Nb-doped TiO₂ (Nb:TiO₂) has received special attention as a transparent conducting oxide (TCO) due to its electrical conductivity at room temperature. Nb:TiO₂ thin films were first reported by Furubayashi *et al.*,² using pulsed laser deposition, several other groups also studied Nb:TiO₂ using sputtering³ and sol-gel spin coating⁴ for TCO applications. The ionic radius of Nb⁵⁺ of 0.064 nm is slightly larger than Ti⁴⁺ of 0.0605 nm; therefore, Nb⁵⁺ works as an n-type dopant in TiO₂ lattice and generates additional carriers in its conduction band. Archana *et al.*⁵ also reported the high electron mobility and optical transparency of Nb–TiO₂, giving rise to the enhancement in charge transport behavior after 2 at.% of Nb doping. Thus, these excess electrons with high mobility could assist the speedy initial reaction of the organic decomposition process, thereby enhancing the overall photocatalytic activity of the Nb–TiO₂ catalyst. Hence, the study of the effect of Nb doping on the photocatalytic activity of TiO₂ appears to be of interest. A literature survey shows very few reports available on Nb:TiO₂ thin film deposition for photocatalytic applications. Mattsson *et al.*⁶ reported the Nb:TiO₂ thin films deposited by sol-gel for decomposition of acetone using visible light. They observed that the decomposition rate of Nb:TiO₂ was smaller than that of TiO₂, even if the Nb:TiO₂ showed higher absorption for visible light. They concluded that the

formation of Nb=O clusters worked as electron-hole recombination centers, making Nb:TiO₂ less photocatalytically active. Archana *et al.*⁷ also discussed carrier recombination centers due to lattice strain raised from the mismatch of Nb and Ti ions with the increase in Nb concentration. In their work, they deposited Nb–TiO₂ nanowires by electrospinning for dye synthesized solar cell application. They showed that the doping of 5 at.% Nb in TiO₂ gave a slight appearance of a rutile phase (<1%) in XRD. The increase in the current density and electron mobility was observed with an increase in Nb concentration from 2 to 5 at.%. However, they observed that the efficiency of cells was reduced due to the lower fill factor and open circuit voltage by the formation of carrier recombination centers due to lattice strain. Yao *et al.*⁸ reported the preparation of >85% transparent Nb:TiO₂ films on glass using DC/RF magnetron co-sputtering. The best photocatalytic activity on methylene blue (MB) was observed for Nb:TiO₂ films annealed at 400°C under visible light irradiation. Porous Nb:TiO₂ microspheres were synthesized by Yang *et al.*⁹ using ultrasonic spray pyrolysis. The photocatalytic activity of these Nb:TiO₂ microspheres was investigated on MB dye, where photocatalytic activity enhanced monotonically with an increase in Nb concentration due to the suppression of electron hole pair recombination.

This article presents the synthesis of Nb:TiO₂ sols using a nonaqueous sol-gel method that firstly involves the complexation of the titanium alkoxide precursor, and secondly involves an *in situ* production of water. In the nonaqueous sol-gel synthesis route, the *in situ* production of water via esterification reaction was initiated due to the addition of acetic acid solution. The advantage of this nonaqueous sol-gel method is that it yields uniform nanoparticles with crystal size in the range of only a few nanometers.¹⁰ Thus, films were prepared by using the abovementioned sol-gel method produce transparent, adherent, homogeneous and photocatalytically active Nb:TiO₂ thin films with a thickness of ~250 nm by spin coating on a glass substrate. The study of the characteristics of transparent TiO₂ and Nb:TiO₂ thin films for photocatalysis application has been carried out. The effect of Nb concentration on the decomposition of MB under UV illumination has been investigated using MB as a model organic pollutant.

II. Experimental Procedure

(1) Preparation of Thin Films

Titanium n-butoxide (1.5 g) was used as a Ti precursor mixed with diethylene glycol (DEG 10 g) and acetic acid (1 g). Furthermore, an appropriate volume of niobium ethoxide was added to aforementioned Ti solution to dope with 3, 7, and 12 at.% of Nb. More than 12 at.% of Nb concentration gave films with cracks and bad adhesion, therefore doping was limited to 12 at.%. Undoped TiO₂ thin films are presented as 0 at.% Nb:TiO₂. After making the precursor, a transparent and homogeneous liquid was formed, which was aged for 24 h. Precleaned soda lime glass (SLG) slides

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(2 cm × 2 cm) were used as a substrate. The precursor solution of 1 ml was dropped on the substrate then spun for 30 s at 4,000 rpm using a spin coater and preannealed at 250°C on a hot plate. This process was repeated ten times to achieve a film with a thickness of ~250 nm. Finally, the films were air annealed using a two-step process in a closed furnace; in the first step, the films were annealed for 15 min at 300°C to remove the DEG effectively, and were then further annealed for 60 min at 500°C for crystallization of TiO₂.

(2) Characterization of Thin Films

The crystalline structures of pure TiO₂ and Nb:TiO₂ thin films were identified by X-ray diffraction (XRD; D/MAX-2005, Rigaku, Tokyo, Japan) with CuK α ($\lambda = 0.154$ nm). Surface morphologies and cross-sectional views of the films were imaged using a scanning electron microscope (HRSEM, XL30SFEG; Philips Co., Amsterdam, Holland). A noncontact mode atomic force microscope (AFM; XE-100, Park Systems Corp., Suwon, Korea) was used to examine the surface morphology and roughness of the spin coated films. Optical absorption in the spectral region of 300–800 nm was assessed using a UV–visible spectrometer (Optizen POP Mecasys Co. Ltd., Dae-Jeon, Korea).

(3) Photocatalytic Experiments

The photocatalytic activities of prepared samples for decomposition of aqueous MB solution were studied under UVA light ($\lambda = 365$ nm, 0.6 mW/cm²). MB solution (#M2661, 0.1 wt% solution in water, Samchun Chemical, Suncheon, Korea) was mixed with deionized water at a 1:200 volume ratio (5 ppm). The aforementioned aqueous MB of about 1.5 ml was evenly poured onto the prepared films before being UVA irradiated. In addition, the MB solution was collected at different time intervals and changes in concentrations were estimated by measuring the intensity of the MB absorption peak at 664 nm using the UV–visible spectrometer.¹¹ Tests were repeated to confirm the reliability of the results.

III. Results and Discussion

The viscosity of sols was measured before thin film deposition using a LVDV-I+CP viscometer (Brookfield). The average viscosity of Nb:TiO₂ sols with Nb concentrations of 0, 3, 7, and 12 at.% was 28.7, 30.5, 33.3, and 35.2 cP, respectively. The increase in viscosity was due to the increase in Nb ethoxide concentration.

The X-ray diffraction patterns of TiO₂ and Nb:TiO₂ films with different Nb concentrations are shown in Fig. 1(a). The anatase phase in all films is confirmed by peaks at $2\theta = 24.9^\circ$, 37.42° , 47.56° , 53.34° , and 54.56° corresponding to the (101), (004), (200), (105), and (211) orientation planes, respectively, which is in agreement with JCPDS card 21-1272. A literature survey shows that the formation of rutile phase depends on deposition method, crystal size, and other processing parameters.¹² Archana *et al.*⁵ and Yang *et al.*⁹ observed a slight trace of the rutile phase in XRD with (110) peak at $2\theta \sim 27.5^\circ$. However, in our case, rutile phase peaks related to TiO₂ or Nb₂O₅ were not observed in Nb–TiO₂ films, and this concurs with the results from previous studies,^{13–15} which implies the incorporation of Nb⁵⁺ into the TiO₂ lattice. The lattice constant calculated using the formulations given by Ghazzal *et al.*¹⁶ is plotted as a function of the Nb concentration shown in Fig. 1(b). Although the lattice constant *a* proportionally increases with Nb concentration, no dependence of lattice constant *c* was observed. The increase in a single lattice constant indicates that the films have tensile stress. The strain (ϵ) effect and residual stress (σ)¹⁶ on the lattice constants that have been calculated from the lattice spacing of anatase films for (101) and (004) orientations are presented in Table I. The crystal

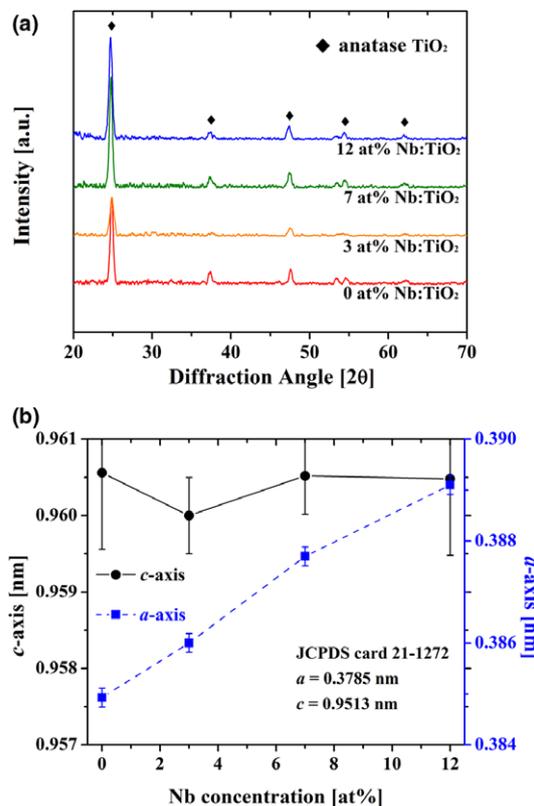


Fig. 1. (a) XRD spectra of Nb:TiO₂ thin films, (b) Effect of Nb concentration on lattice constant of Nb:TiO₂ thin films.

Table I. Comparison of Lattice Constant, Strain, Stress, and Crystal Size Determined from XRD

Sample	Strain (10^{-3})		Stress (GPa)	
	$\epsilon_{(101)}$	$\epsilon_{(004)}$	$\sigma_{(101)}$	$\sigma_{(004)}$
JCPDS (21-1272)	0	0	0	0
0 at.% Nb:TiO ₂	-15.1	-9.84	-7.48	-4.88
3 at.% Nb:TiO ₂	-16.7	-9.25	-8.27	-4.59
7 at.% Nb:TiO ₂	-21.5	-9.8	-10.6	-4.86
12 at.% Nb:TiO ₂	-24.7	-9.76	-12.3	-4.84

size calculated by Scherrer's formula decreased slightly from 19.8 to 18.6 nm with increasing Nb concentration. The (101) orientation peak at 25.28° mentioned in JCPDS card 21-1272 was slightly shifted to the lower 2θ (24.9°) for pure TiO₂. This shift could be attributed to the formation of stress, as shown in Table I. The incorporation of higher ionic radius Nb⁵⁺ ion into the TiO₂ crystal lattice results in a shift of the anatase (101) peak to a lower value compared to pure TiO₂.

The first row in Fig. 2 shows the SEM images of the surface morphology of Nb:TiO₂ thin films. The films consist of a fairly uniform granular structure. As observed in XRD, the SEM images also show the reduced grain size with increasing Nb concentration. The second row in Fig. 2 shows the 3D AFM images of Nb:TiO₂ thin films with varying Nb concentrations. The average roughness (R_a) of films that was acquired from a $2.5 \mu\text{m} \times 2.5 \mu\text{m}$ scanned area of films is presented with each AFM image.

Figure 3 shows the transmittance spectra of the TiO₂ and Nb:TiO₂ films at room temperature. The measurements were taken at normal incidence using bare SLG substrate as a reference. The average transmittance of each film in the visible range (400–800 nm) is presented in Table II. The film's color changed from transparent pink to faint green with the increase in Nb concentration, as shown in the inset in Fig. 3. Table III shows the direct optical band gap energy of thin films obtained by plotting a square of absorption coefficient

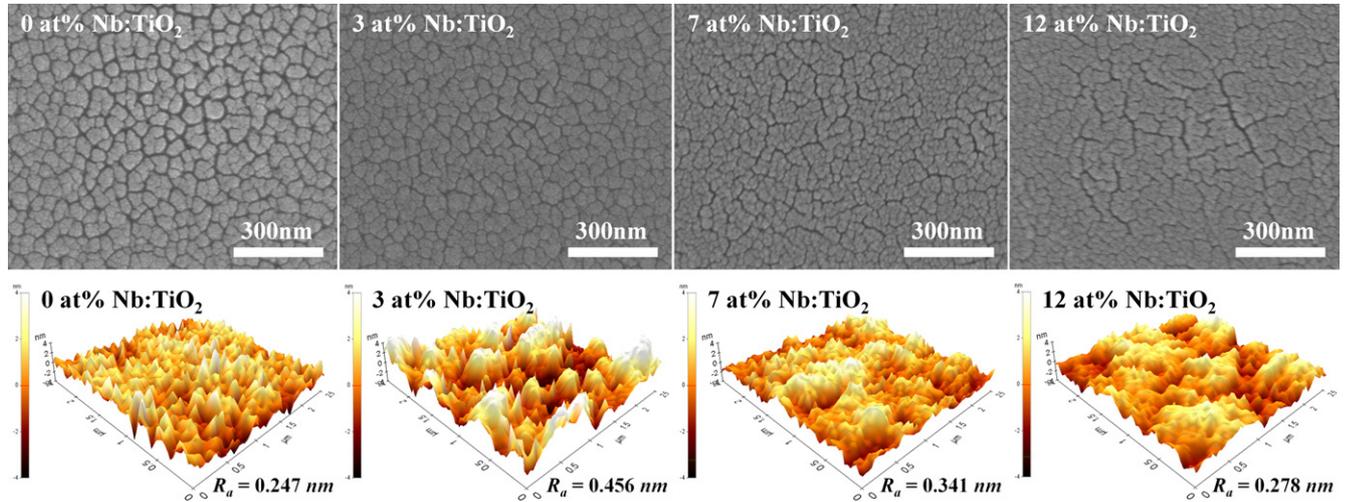


Fig. 2. The up row shows SEM surface images and bottom row presents 3D view of AFM for various Nb concentrations.

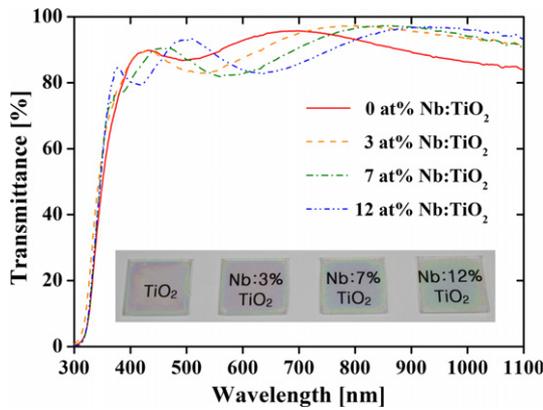


Fig. 3. UV-Visible transmittance spectra for different concentrations of Nb:TiO₂ thin films.

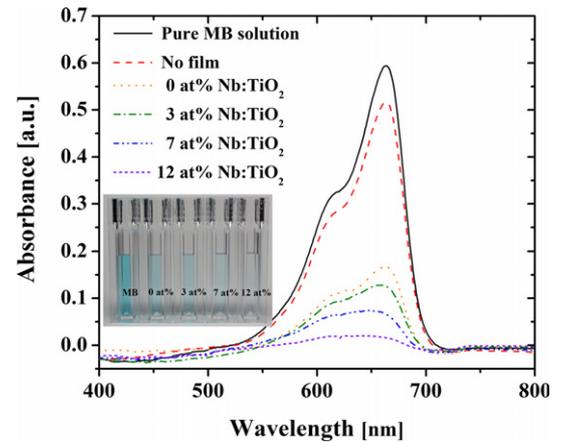


Fig. 4. Effect of Nb concentration on MB degradation after 2 h of UV illumination.

Table II. Influence of Nb Concentration on Transmittance Averaged in Visible Range (400 λ <math>< 800</math> nm) and Band Gap of Nb:TiO₂ Thin Films

Sample	Average transmittance (%)	Band gap (eV)
0 at.% Nb:TiO ₂	91.08	3.84
3 at.% Nb:TiO ₂	87.96	3.87
7 at.% Nb:TiO ₂	86.8	3.82
12 at.% Nb:TiO ₂	86.3	3.81

Table III. Reaction Parameters of Photocatalysis for Nb:TiO₂ Thin Films

Sample	k (min ⁻¹ × 10 ⁻³)	D (%)
0 at.% Nb:TiO ₂	9.0	71.8
3 at.% Nb:TiO ₂	10.6	78.9
7 at.% Nb:TiO ₂	14.8	89.1
12 at.% Nb:TiO ₂	24.3	97.3

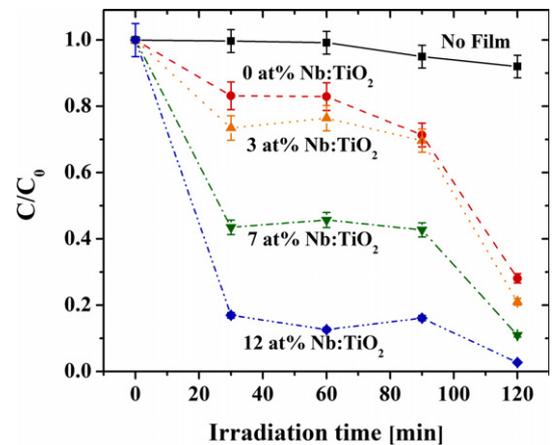


Fig. 5. Photocatalytic degradation of MB as a function of time for various Nb:TiO₂ doping concentrations.

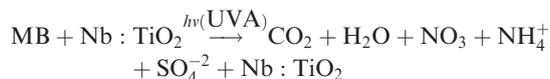
(α^2) as a function of photon energy ($h\nu$) and by the intersection of the linear part of the curve and the horizontal axis. The band gap value for undoped TiO₂ concurs with the results found by Malengreaux *et al.*¹⁷ for TiO₂ thin films using the nonaqueous sol-gel method using a TTIP precursor on SLG. However, after doping of Nb, the band gap variation was minimal; this could be due to the small crystal size as well as the stress formed in the crystal.

Figure 4 shows the photocatalytic activities of different concentrations of Nb:TiO₂ thin films from the decolorization of aqueous MB dye after 2 h of UVA irradiation. The presence of the characteristic absorption peak of MB at 664 nm decreased with increasing Nb concentration. The highest degradation of MB is observed for the 12 at.% Nb:TiO₂ thin film. As expected, MB degradation in the absence of a catalyst film was negligible after 2 h of UV irradiation. The inset of Fig. 4 represents the

Table IV. Comparison of Nb:TiO₂ Thin Films with Previous Photocatalysis Work

Author	Method and other paramters	Organic pollutant	Light and intensity	Irradiation time (h)	Remark
Mattsson <i>et al.</i> ⁶	Sol-gel Annealing 450° for 30 min in air	Acetone	Visible light by Xenon arc lamp using AM (1.5) filter with intensity 166 mW/cm ²	0–1	Degradation of Acetone is possible by pure TiO ₂ only Nb doping in TiO ₂ formed Nb=O clusters which act as recombination sites lowering the photocatalytic activity
Yao <i>et al.</i> ⁸	DC/RF co-sputtering annealing at 400 and 500°C for 1 h in air	MB (1.337 × 10 ⁻³ M, volume 3 ml)	Visible light bulbs (NEC, FL15EX-D-X)	0–48	Nb:TiO ₂ films annealed at 400°C showed good photocatalytic activity
Yang <i>et al.</i> ⁹	Ultrasonic spray pyrolysis microspheres	MB	Visible light by Xenon lamp with cutoff filter of 400 nm and output intensity 67 mW/cm ²	0–3	5 mol% Nb:TiO ₂ films shows better photocatalytic activity in solar and visible light
Kaleji <i>et al.</i> ¹³	Sol-gel dip coating 475°C for 1 h in air	MB concentration 5 ppm	UV lamp with 360 nm wavelength and 8 W intensity	0–2	1 mol% of Nb:TiO ₂ films showed better photocatalytic activity
The present work	Nonaqueous sol-gel annealing at 500°C for 30 min in air	MB Concentration 5 ppm (1.5 ml)	UV 365 nm light with intensity 0.6 mW/cm ²	0–2	12 at.% Nb:TiO ₂ films showed 97.3% MB degradation in 2 h of UV irradiation

decolorization of MB compared to the original solution. The reaction mechanism of photocatalytic decolorization of MB in the presence of Nb:TiO₂ can be explained in a similar manner as that of TiO₂, as explained in our earlier reports.¹ However, the enhancement in photocatalytic activity after Nb doping is likely due to an increase in carrier electrons from pentavalent Nb. This increase in electron concentration in Nb:TiO₂ thin films consequently gives a faster reaction by forming more superoxide radicals. The formed hydroxyl and superoxide radicals react with MB to yield degradation products such as CO₂, NO₃, NH₄⁺, and SO₄⁻². Thus, the final reaction can be represented in the following way:



The time dependency of C/C_0 under UV irradiation using Nb:TiO₂ thin films for different Nb concentrations is shown in Fig. 5 where C is the concentration of MB after different irradiation time (t in min) and C_0 is the initial MB concentration. The photocatalytic degradation of MB solution by Nb:TiO₂ thin films under UV irradiation can be modeled using the Langmuir–Hinshelwood (LH)¹⁸ reaction kinetics. For low concentration MB solution the LH reaction can be expressed in terms of a pseudo first-order reaction $\ln(C_0/C) = kt$ and the apparent reaction rate constant ' k ' can be obtained from the fitted straight line plots of $\ln(C_0/C)$ versus t . Table III clearly reveals that the apparent reaction rate constant ' k ' and degradation efficiency ' D ' increases with escalation in Nb concentration. After 2 h of UV irradiation 12 at.% Nb:TiO₂ thin film exhibited highest rate constant of $24.3 \times 10^{-3} \text{ min}^{-1}$, which was twice that of undoped TiO₂. As mentioned earlier, the pentavalent Nb⁵⁺ ion doping in TiO₂ introduces more electrons in the conduction band and some shallow donor levels below the conduction edge. These extra electrons give more superoxide radicals consequently enhancing the photocatalytic efficiency of Nb:TiO₂ thin films.

Table IV compares the photocatalytic study of Nb:TiO₂ thin films carried out by previous studies. The transparency in our case for undoped and doped samples was greater than 86%. In addition, 97.3% of MB degradation was observed in 2 h of UVA irradiation for 12 at.% of Nb:TiO₂ thin films.

IV. Conclusions

Transparent Nb:TiO₂ thin films were deposited successfully using the nonaqueous sol-gel technique. XRD analysis confirmed the presence of only the anatase phase of TiO₂ in both the TiO₂ and Nb:TiO₂ films. The crystal size decreased with an increase in Nb concentration. The highest photodegradation efficiency of 97.3% was observed for 12 at.% Nb:TiO₂ thin films after 2 h of UV irradiation and the reaction rate was two times higher than that of undoped TiO₂.

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